



Analytics for Compound Semiconductors

SiC in Focus

Steve Zamek 6/29/24

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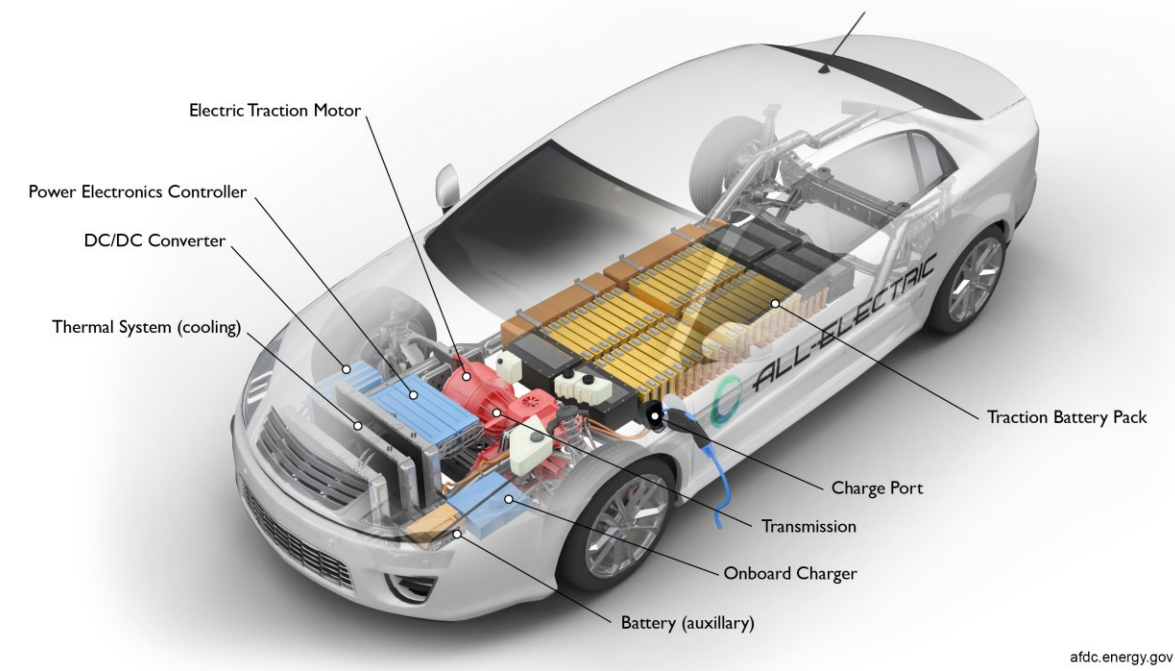
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SiC Industry at a Glance

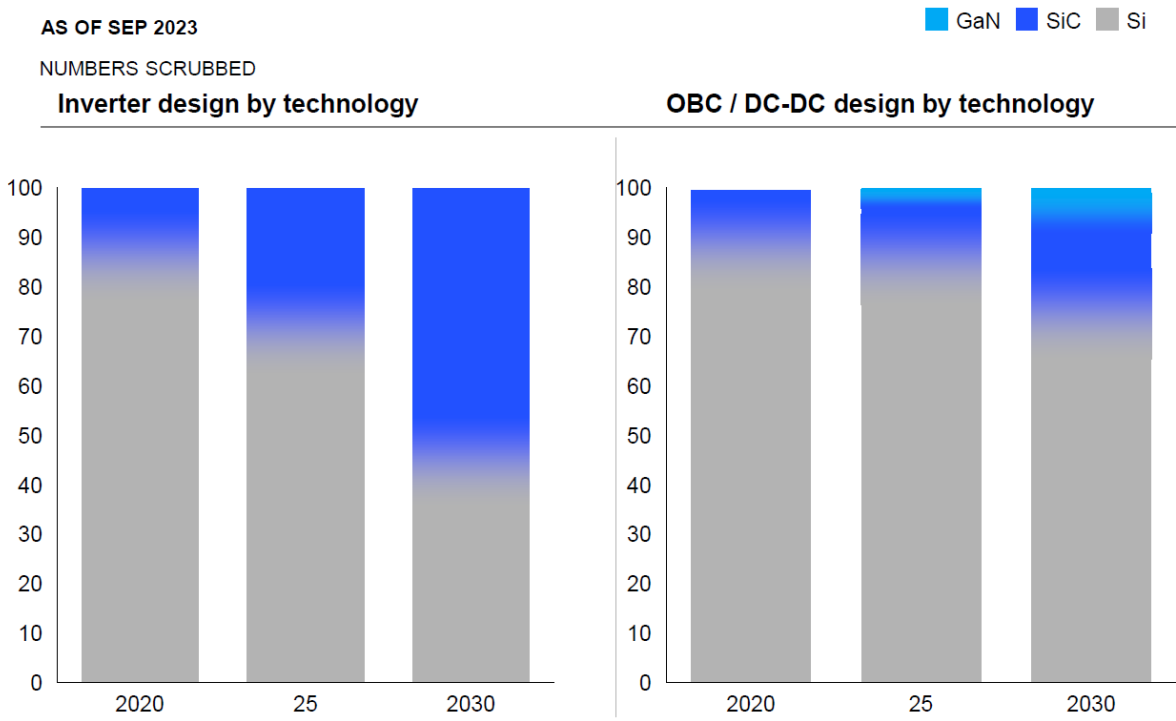
Demand driven mainly by Electric Vehicles

All-Electric Vehicle



source: <https://afdc.energy.gov/vehicles/how-do-all-electric-cars-work>

Projected 25x demand growth out to 2030

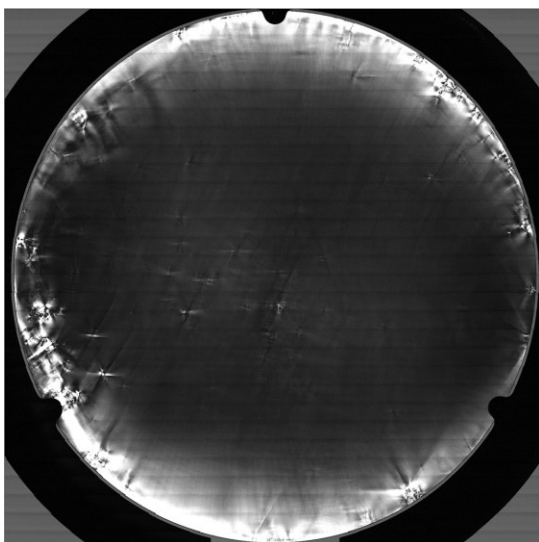


source: McKinsey Center for Future Mobility, Sep 2023

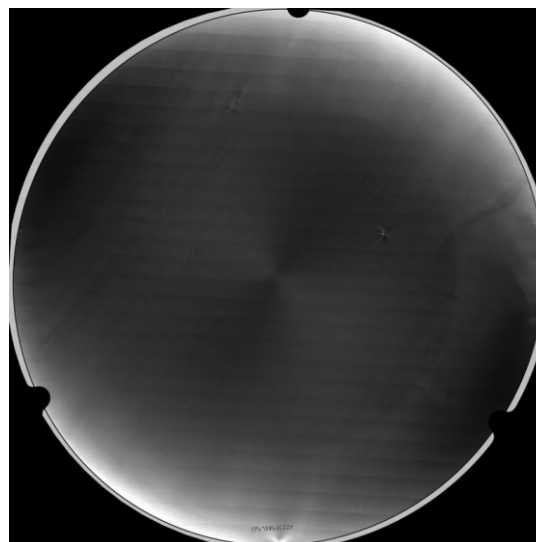
SiC Industry at a Glance

The next 10 years: substrate quality will remain a challenge as the industry is moving to 200 mm wafers

200 MM WAFER; XPOL IMAGE: 2019

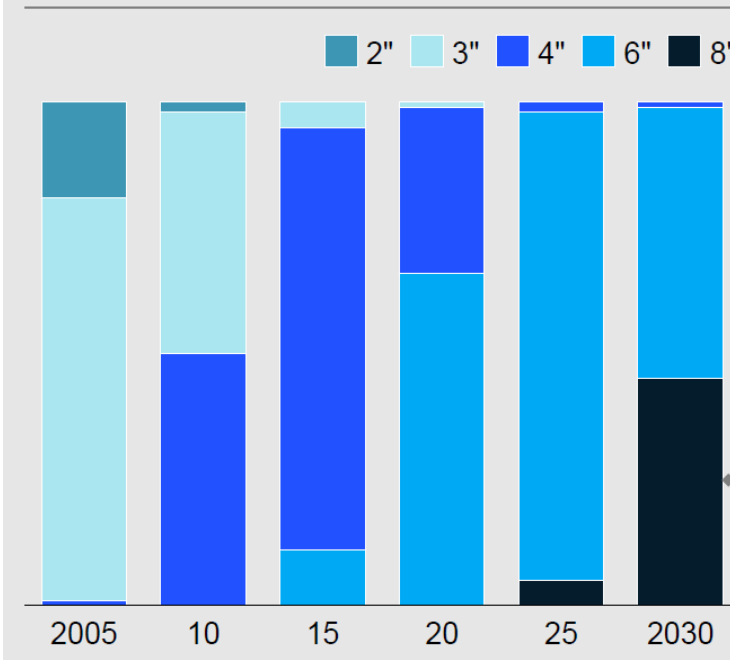


200 MM WAFER; XPOL IMAGE: 2022



source: Wolfspeed, SEMI Webinar, May 2023

SiC wafer diameter evolution, Annual capacity – 8" eqv. (K units), % of total SiC wafers shipped

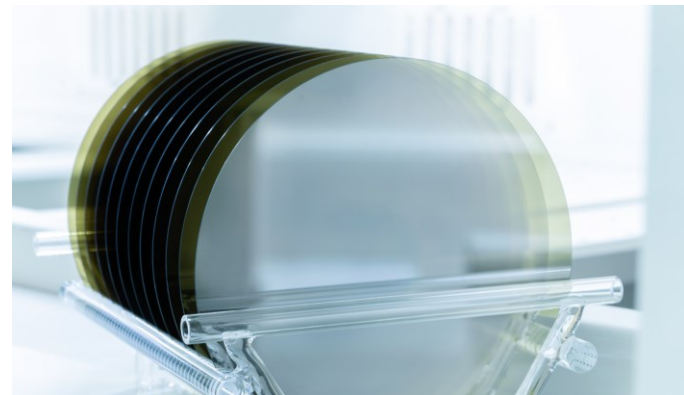


source: McKinsey Center for Future Mobility, Sep 2023

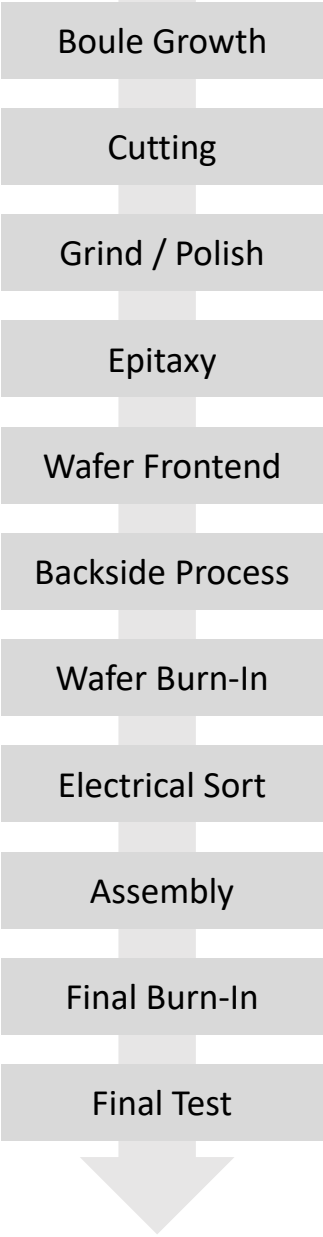
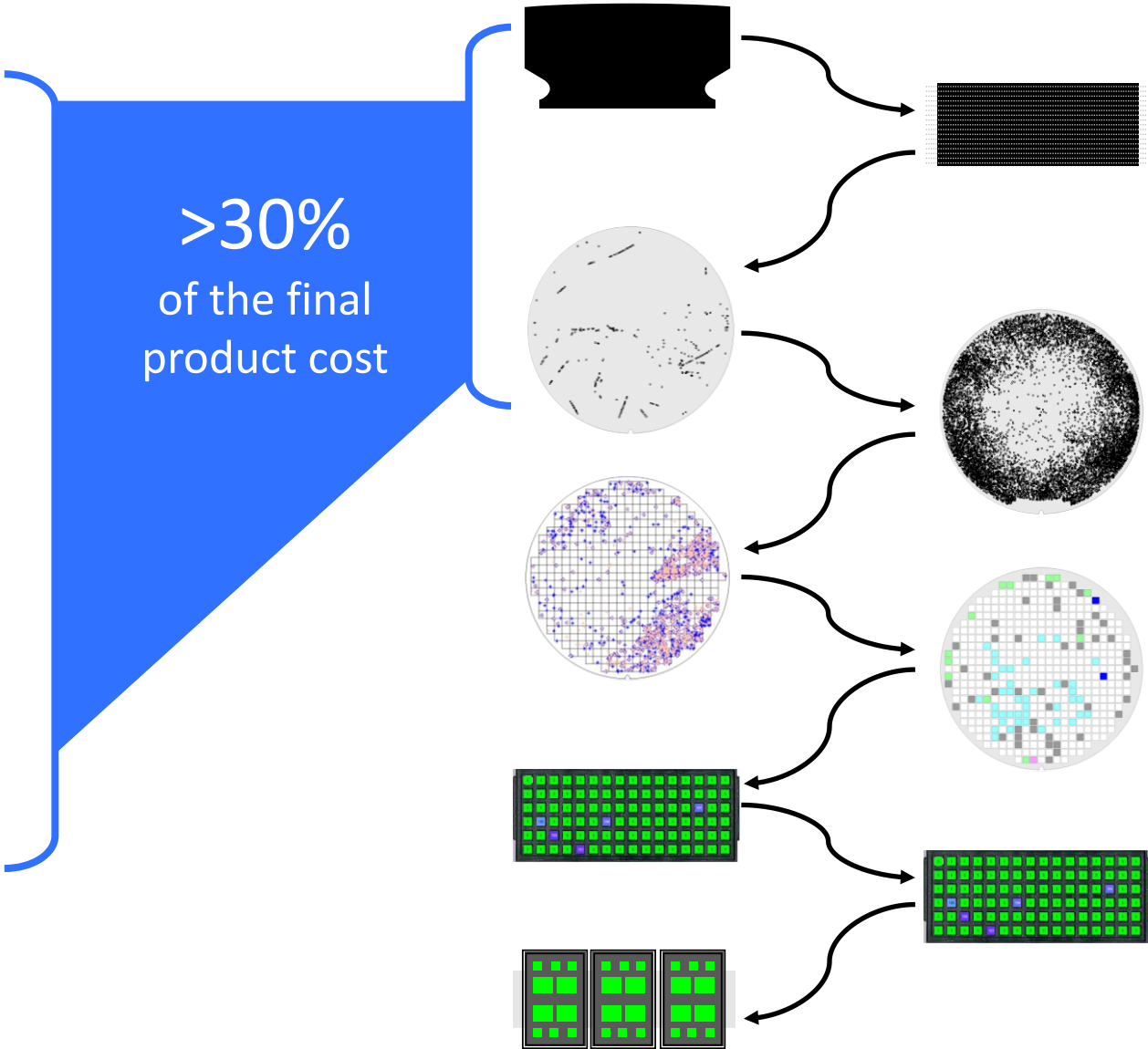
SiC Manufacturing Process Flow



source: CompoundSemiconductors.net, 2017

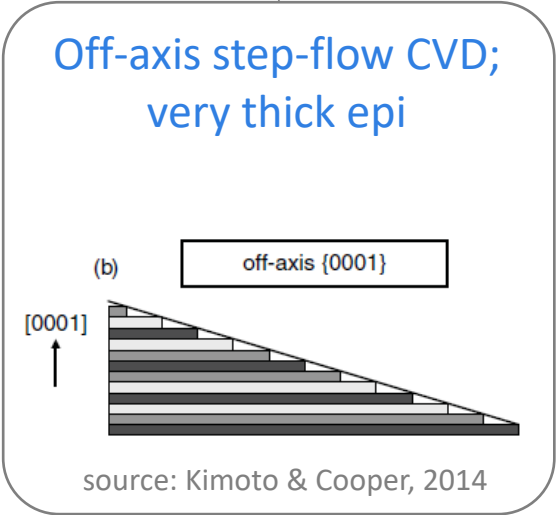
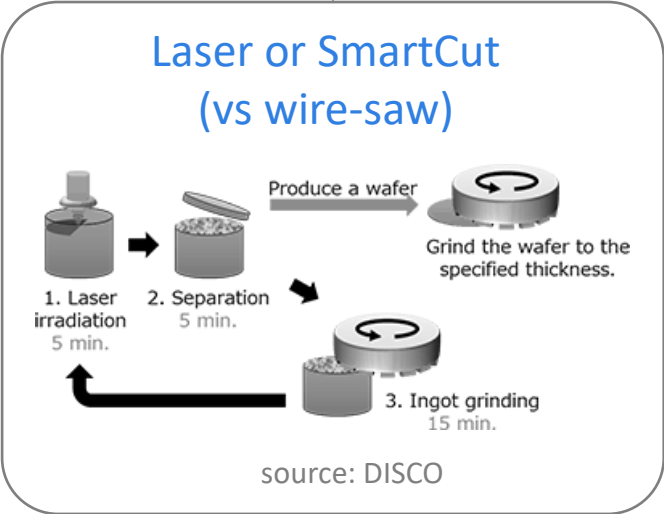
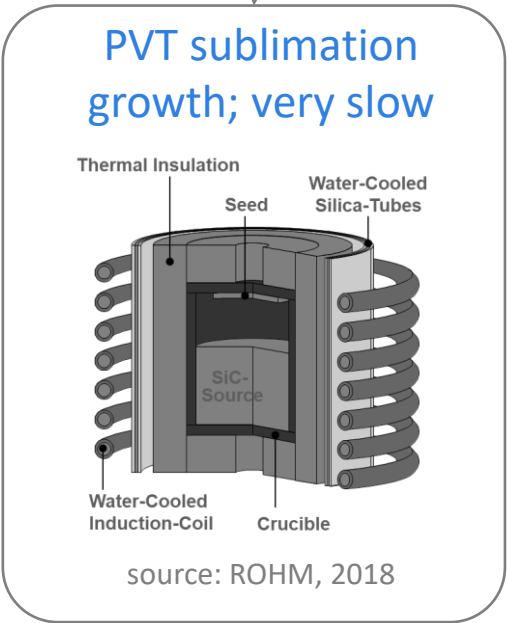
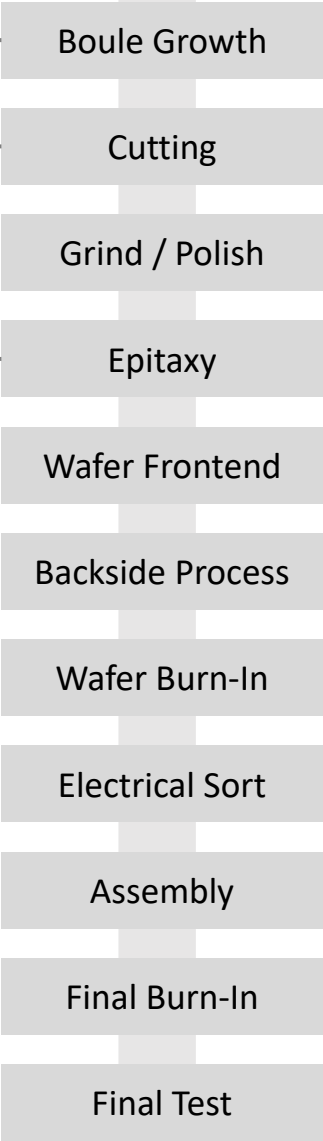


source: SICC, 2024



Challenges in SiC Manufacturing

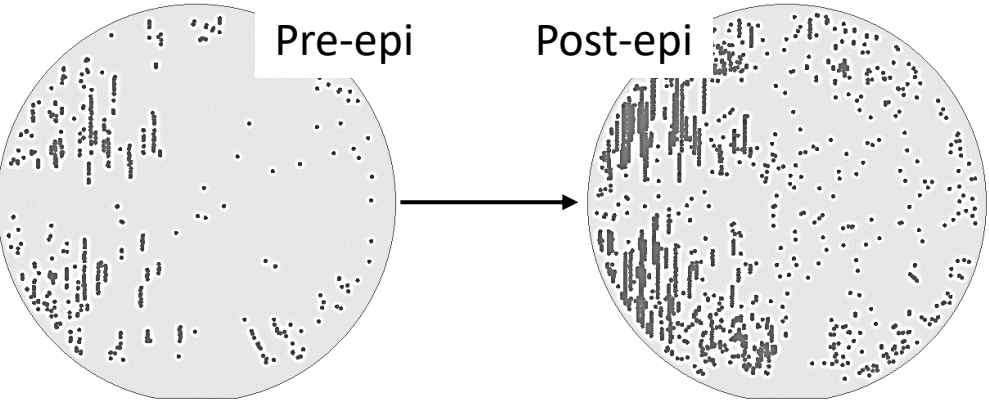
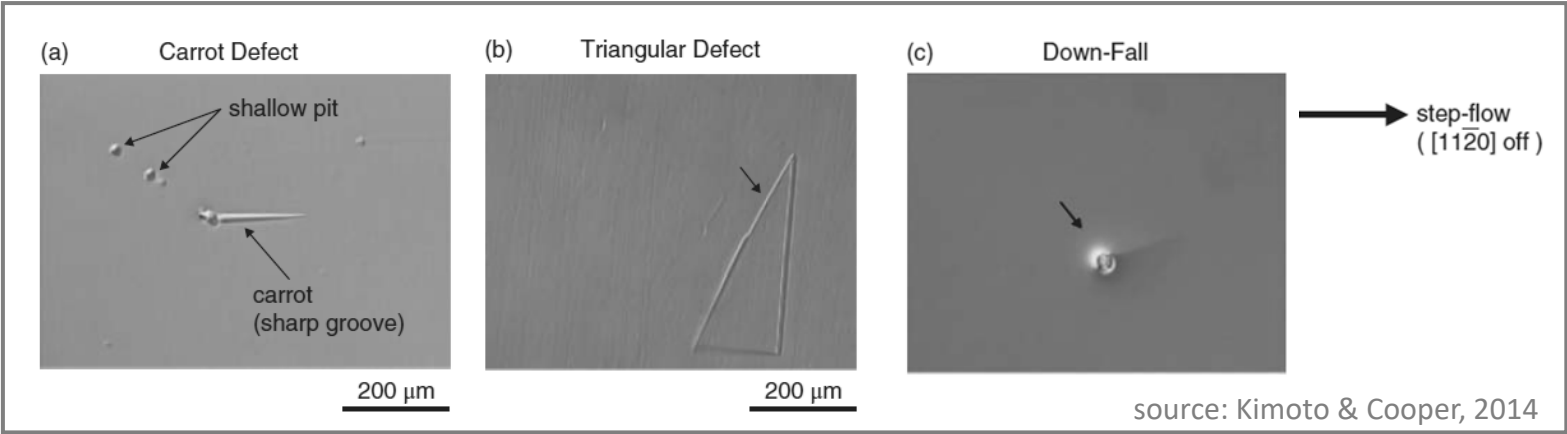
SiC poses unique challenges to manufacturers with high defectivity at all steps



Unique Substrate Defects

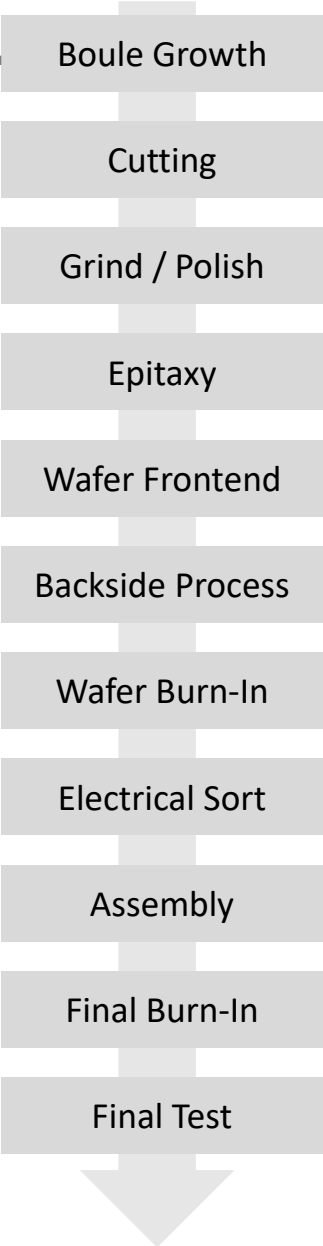
Extended boule defects

- Micropipe
- Threading screw dislocation (TSD)
- Threading edge dislocation (TED)
- (Perfect) Basal plane dislocation (BPD)



Defect Inspection

- Defect Analytics
- Yield Impact
- Substrate Grading



Who We Are

Top 50 Equipment suppliers use
Cimetrix by PDF for connectivity

Top 6 Foundries Run on PDF
Solutions Technology

18 of Top 20 Semi Companies
use PDF Solutions Products

>55K Fab
tools connected
using Cimetrix

>40K process tools
under PDF process
control across the
ecosystem

>350 customers in 20
countries in Fabless,
IDM, Foundry, OSAT,
and System

Leading solution for
die traceability
through the supply
chain

Fastest growing
company in
manufacturing test
operations



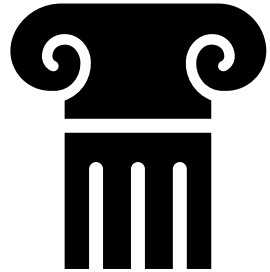
Our Solutions for SiC Manufacturing Analytics

“SiC is where silicon was decades ago...”

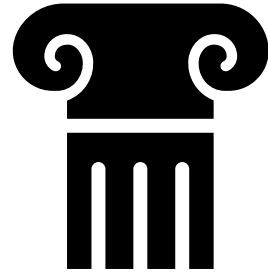


Accelerate your development with analytics

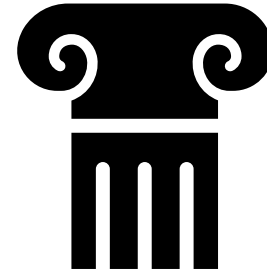
Solutions for Silicon Carbide Manufacturing



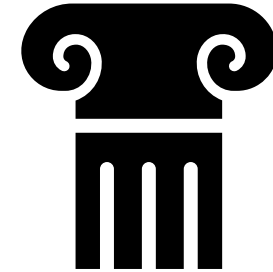
Equipment
Connectivity +
Process Control



Inline + Test Data
Management
Defect | Binmap



Lot Genealogy +
Wafer Level
Traceability



ModelOps
with AI/ML

How We Do It

Proven track-record of interfacing with majority of Manufacturing Execution Systems		
Material Hierarchy	Meta Data	Equipment History
Technology Family Process Product Source Lot Lot Wafer # Die	Equipment Operator Program Recipe Date/Time Process Flow Stages Steps	Equipment TrackIn/Out Recipe Operator Chamber Rework Reticle

CamStar
PROMIS
Oracle
IBM Si View
WorkStream
FACTORYWorks
StationWorks
Wonderware
Miracom
APEX
...

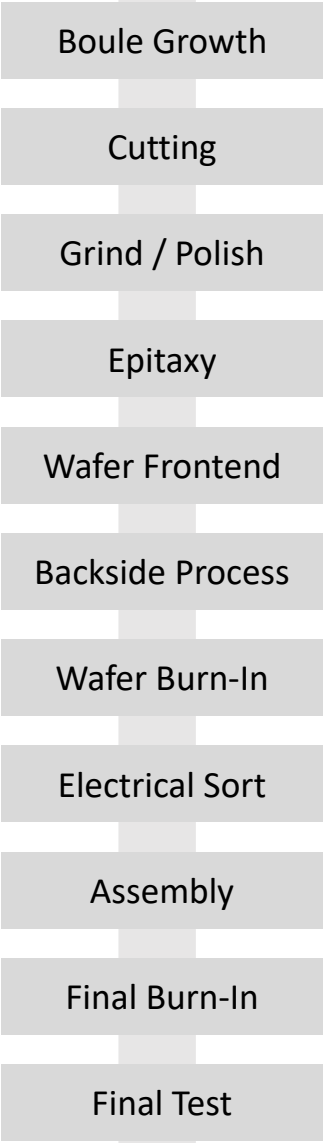


Inline Data
Defect & Metrology

Equipment Sensor
Data (FDC)

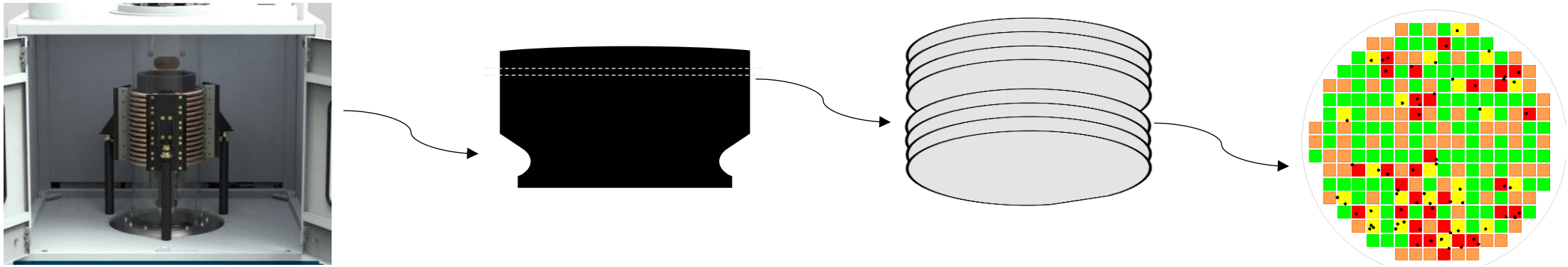
Electrical Data:
PCM | WAT | Binmap

Assembly Data
Die Level Traceability | E142



Big Data
Manufacturing
Analytics platform

Exensio™ Equipment Process Control for SiC

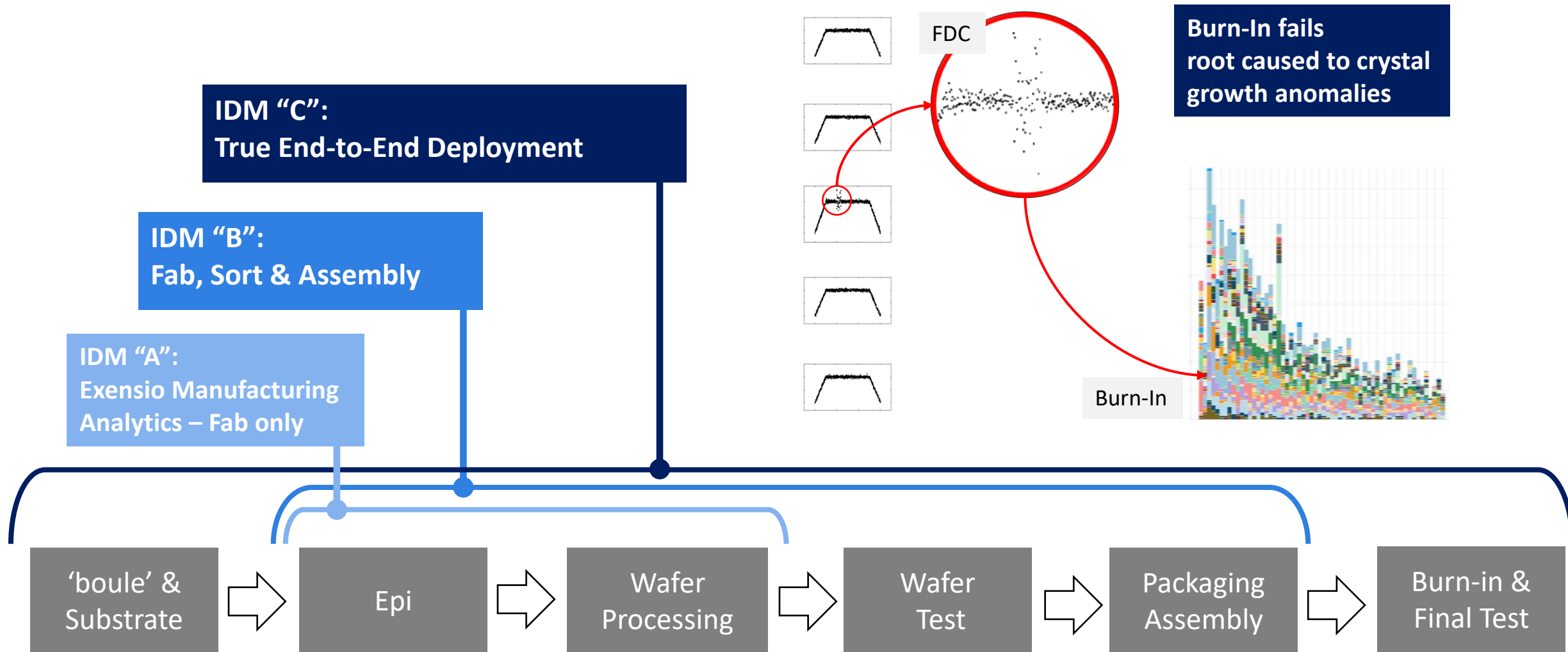


Bring all data under one roof
Use modern data analytics

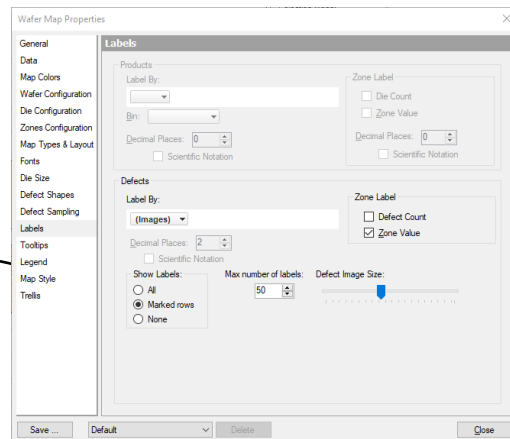
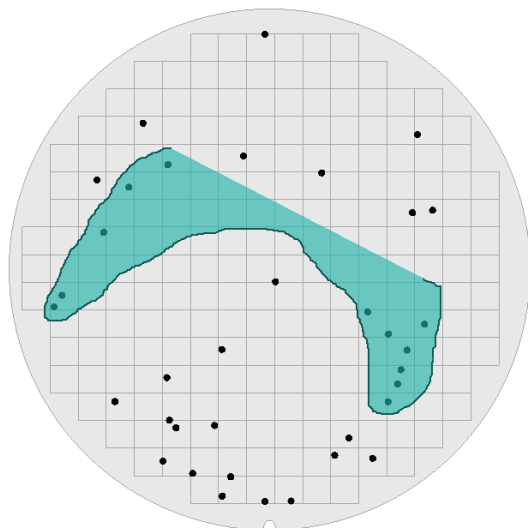


Establish correlations
Identify root-cause of low yield

Deployment Examples in SiC Manufacturing



Defect Management Tools



Defect classification

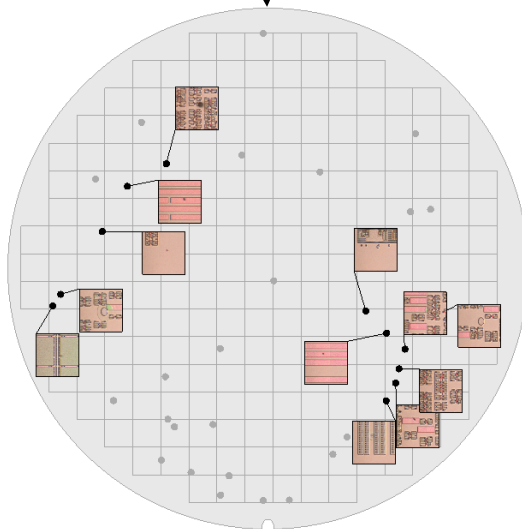
Filter by: Filter string:
 Method: Tag by name:
☐ Add if not found

Code	Name	Critical
-2	1	Y
-2	10	Y
-2	101	Y
-2	102	Y
-2	11	Y
-2	111	Y
-2	112	Y
-2	113	Y
-2	17	Y
-2	19	Y
-2	2	Y
-2	200	Y
-2	22	Y
-2	226	Y

☐ Move to next row ☐ Refresh after commit

- Defects can be reclassified
- Newly generated defects can be exported into new KLARF
- Defect class codes can be redefined in the database

- Powerful tools:**
- Selections
 - Markings
 - Labeling
 - Sampling



Defect image gallery

Defect : 1, Processing Step : LYR1, size : 3.9939999999999999, layer_of_origin : LYR1, roughbin : roughbin_1, finebin : finebin_245

Defect : 5, Processing Step : LYR1, size : 0.624000012874603, layer_of_origin : LYR1, roughbin : roughbin_3, finebin : finebin_245

Defect : 6, Processing Step : LYR1, size : 1.87199997901917, layer_of_origin : LYR1, roughbin : roughbin_1, finebin : finebin_245

Defect : 7, Processing Step : LYR1, size : 0.624000012874603, layer_of_origin : LYR1, roughbin : roughbin_2, finebin : finebin_245

Defect : 5, Processing Step : LYR1, size : 0.624000012874603, layer_of_origin : LYR1, roughbin : roughbin_3, finebin : finebin_245

Data table : Defect

Marking : Marking

Filters : Source

(All) 5 values

Unknown

SEM Internal

SEM External

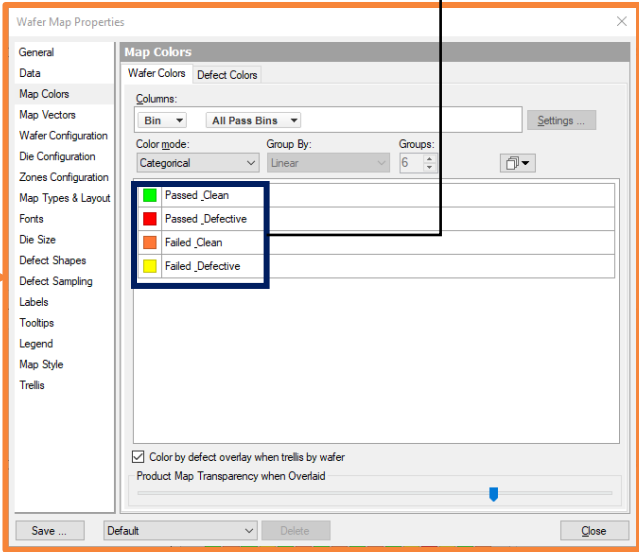
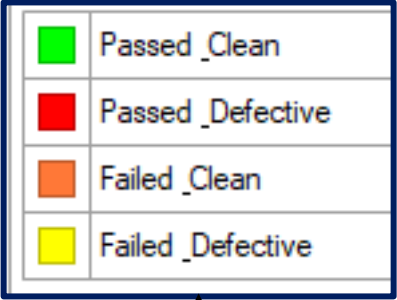
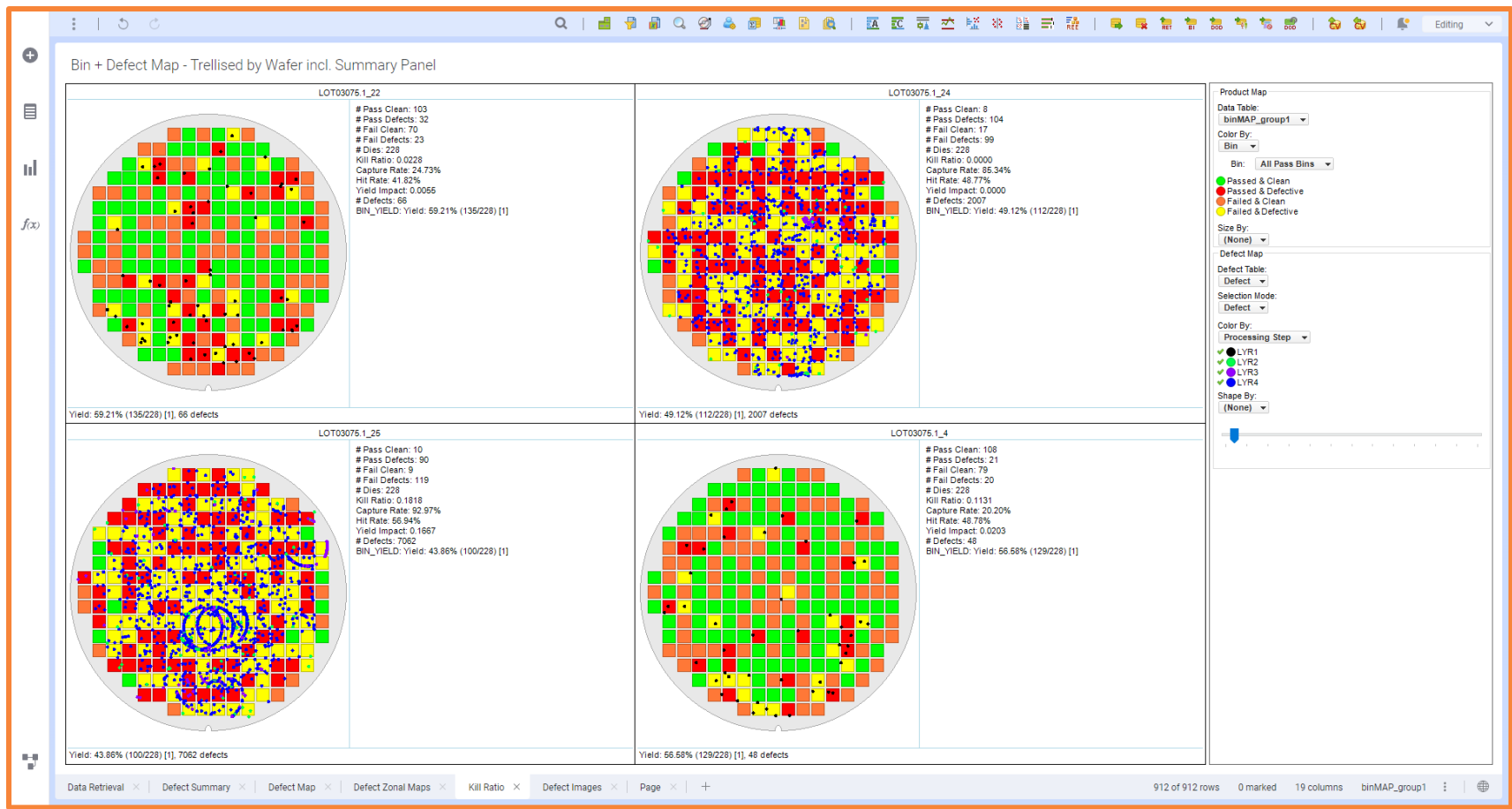
FDX

Image Adjustments : Brightness, Contrast

☒ Gray Scale ☒ Invert Colors

Fill 100% 27%

Defect | Binmap Overlays

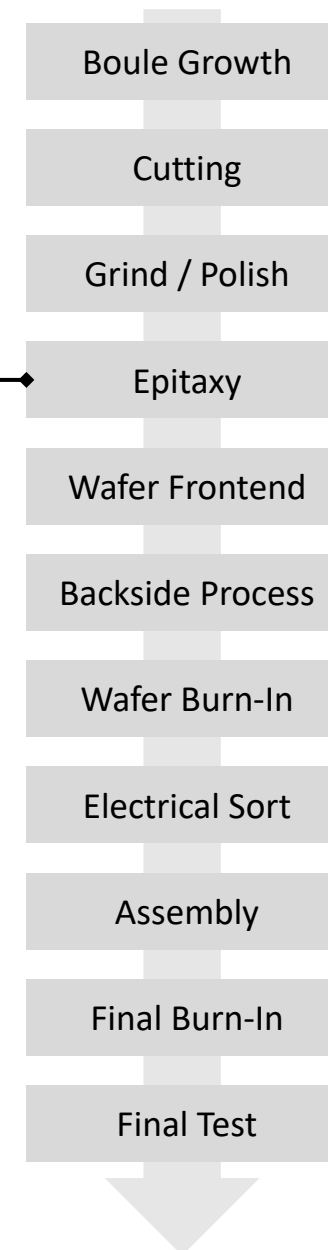
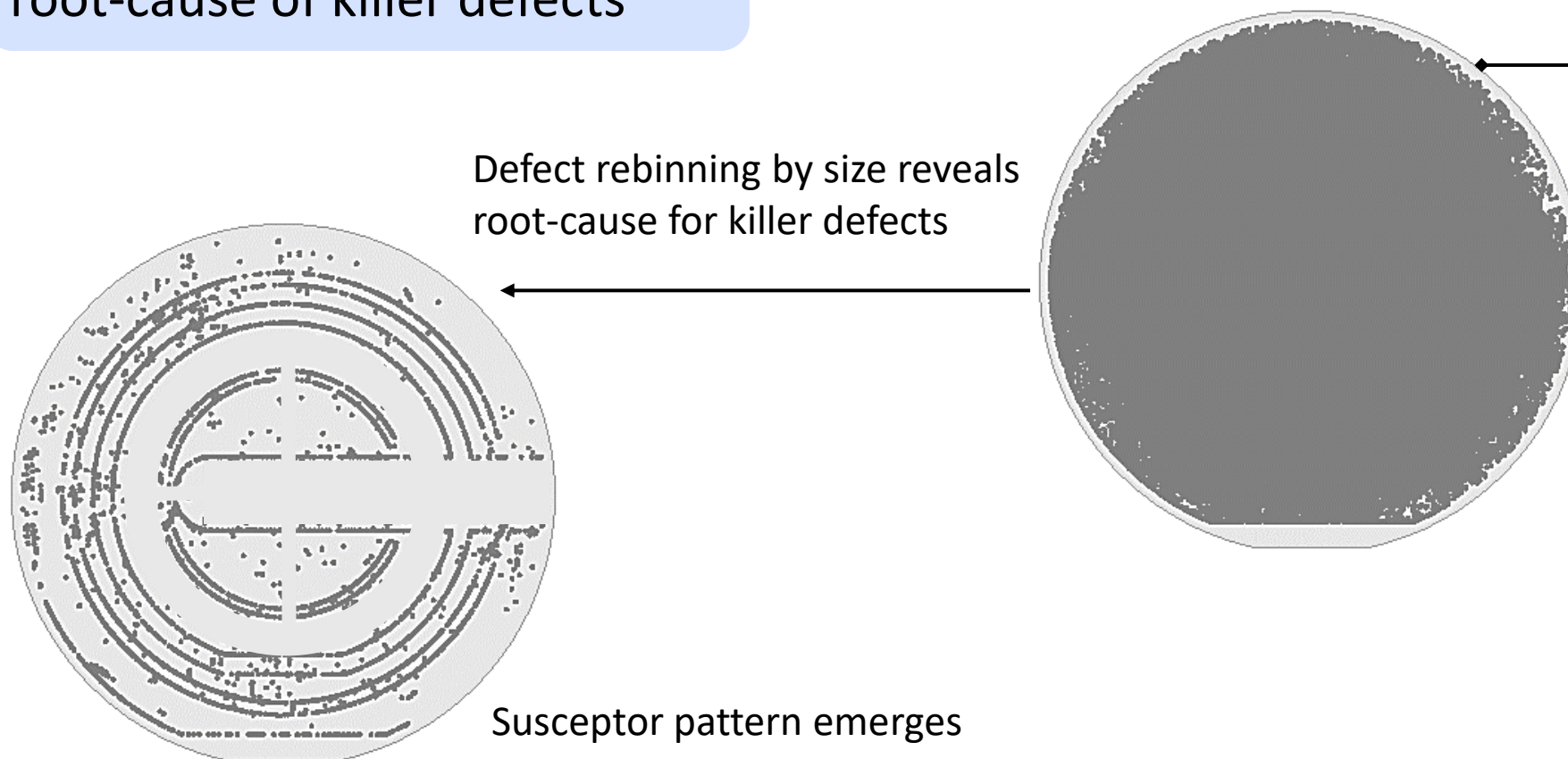


Defect | Binmap Overlays



Exensio™ Defect Management for SiC

Customer use case: identified root-cause of killer defects



Summary

■ The next 5 years in SiC

- SiC CAGR outpaces semiconductors as a whole
- Defectivity will remain high
- Steeper challenges in transition to 200 mm wafers

■ Our solutions

- Exensio is the #1 platform for data analytics across semiconductor manufacturing
- Continued adoption for SiC
- Those with end-to-end deployments will grow faster



Product portfolio:

- Equipment connectivity
- Manufacturing analytics
- Process Control
- Test Operations
- Assembly Operations
- AI & ModelOps

Services:

- Data Integration
- Site, tools, data audit
- Building templates
- Classes and training

Thank You

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